

ABSTRACT OF THE INVENTION

The present invention relates a method of easily fabricating a grating device having a desired reflection characteristic, and the like. In this fabrication method, the phase grating mask is relatively shifted along the longitudinal direction of the optical waveguide by a distance of one half of the grating period of the phase grating mask during the refractive index change inducing light is irradiated on the optical waveguide through the phase grating mask.